



Recent activity from KoALICE



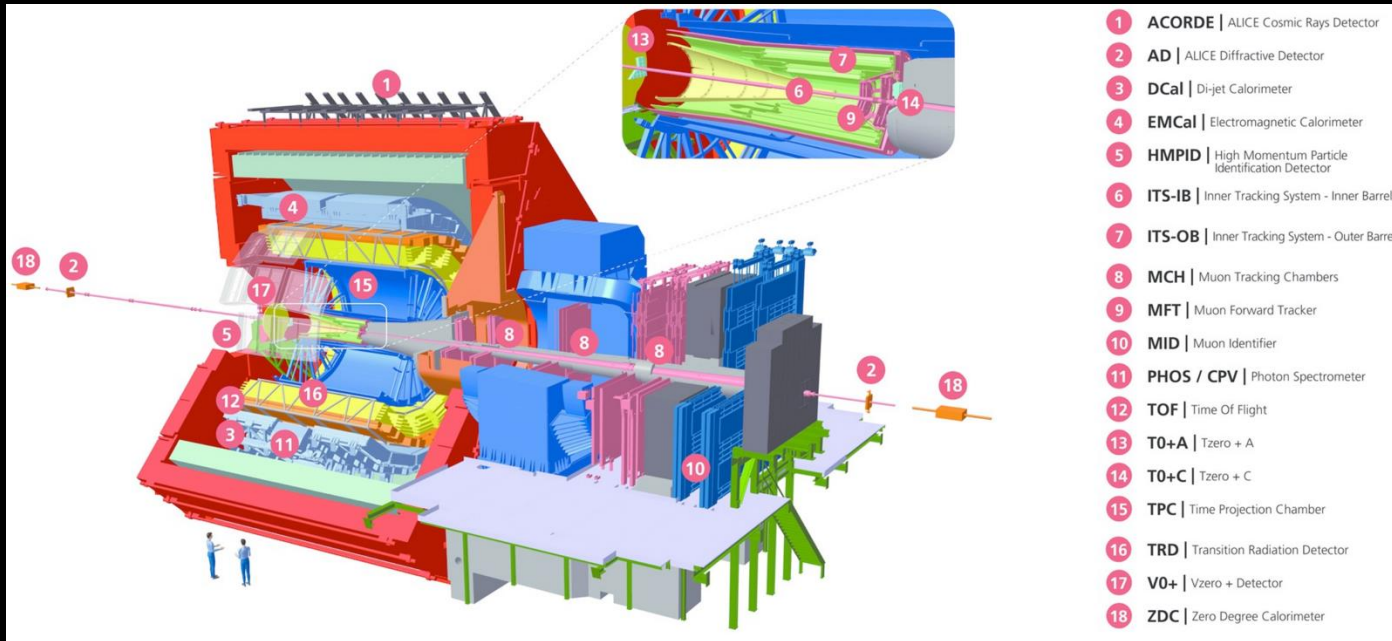
ALICE

Run 3 Pb-Pb
 $\sqrt{s_{NN}} = 5.36$ TeV

27 September 2023, 04:50

Sanghoon Lim
for the KoALICE group

Pusan National University



ALICE review paper

CERN-EP-2022-227

27 October 2022



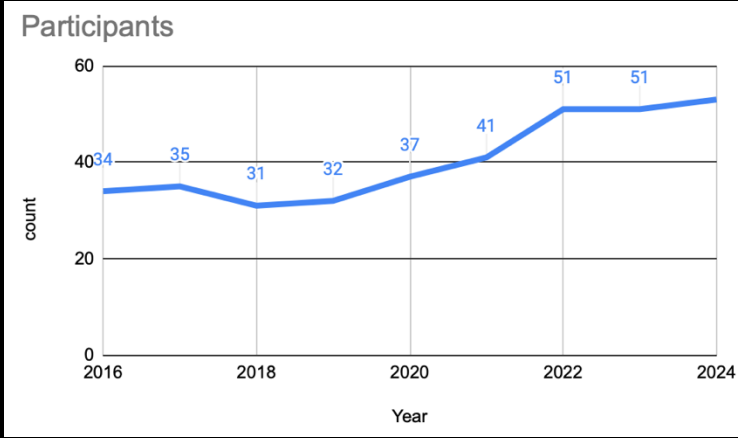
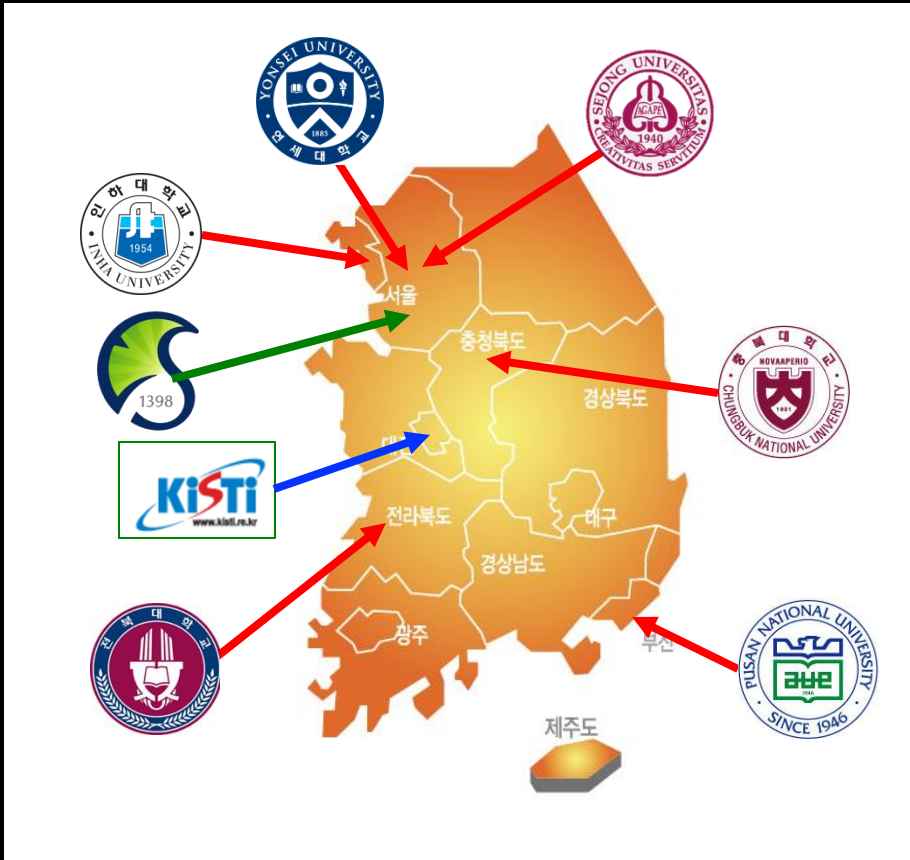
The ALICE experiment: A journey through QCD



arXiv:2211.04384

- Central Barrel: tracking, particle ID, and EM calorimetry ($|\eta| < 0.9$)
- Forward muon arm ($2.5 < \eta < 4.0$)
- Major upgrades in LS2: New inner tracking system, forward muon tracker, and TPC upgrade

arXiv:2302.01238



KoALICE in numbers (53+1)

18 PhD Physicists (18 M&O-A)

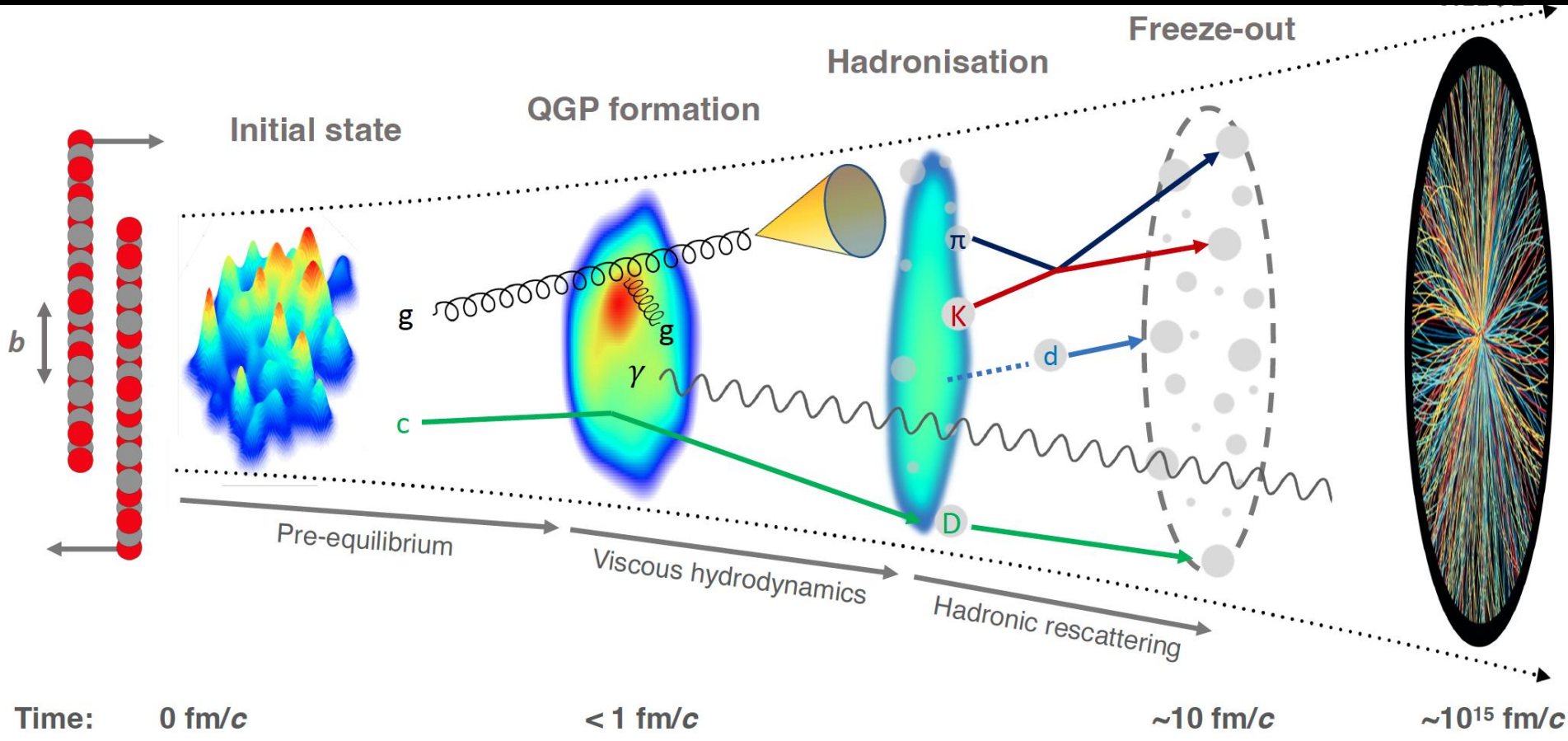
10 PhD Students

23 Master Students

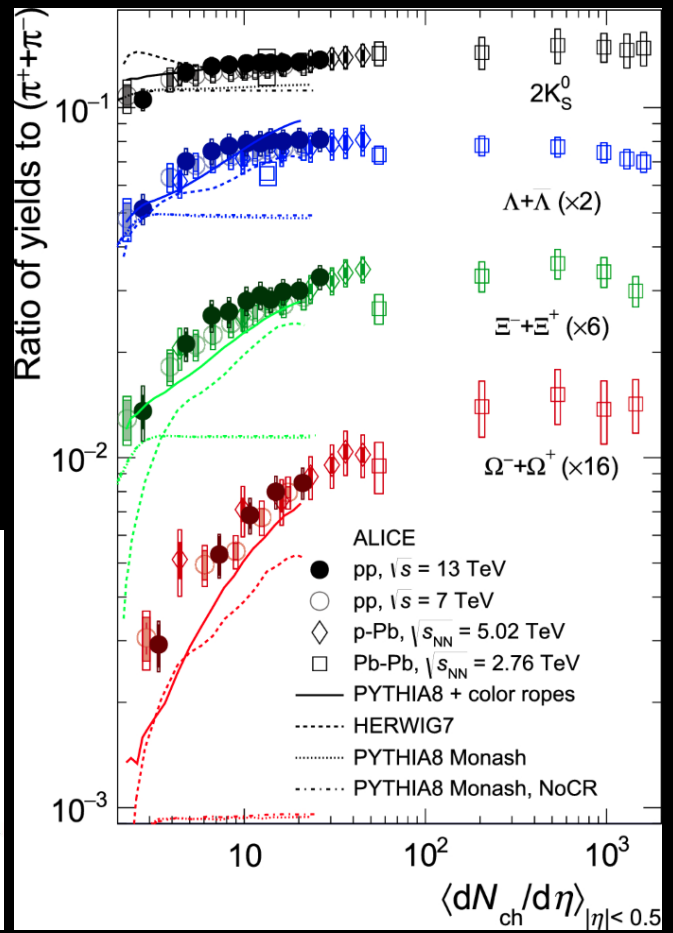
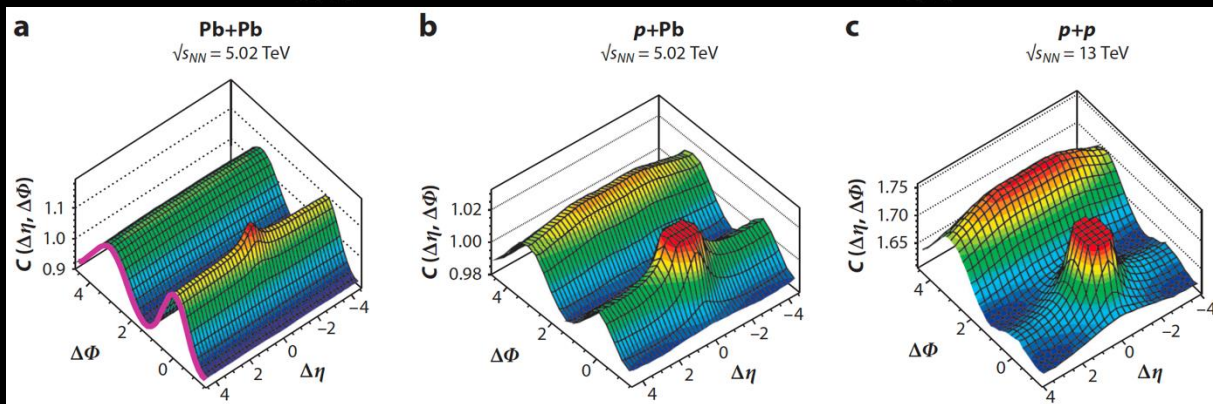
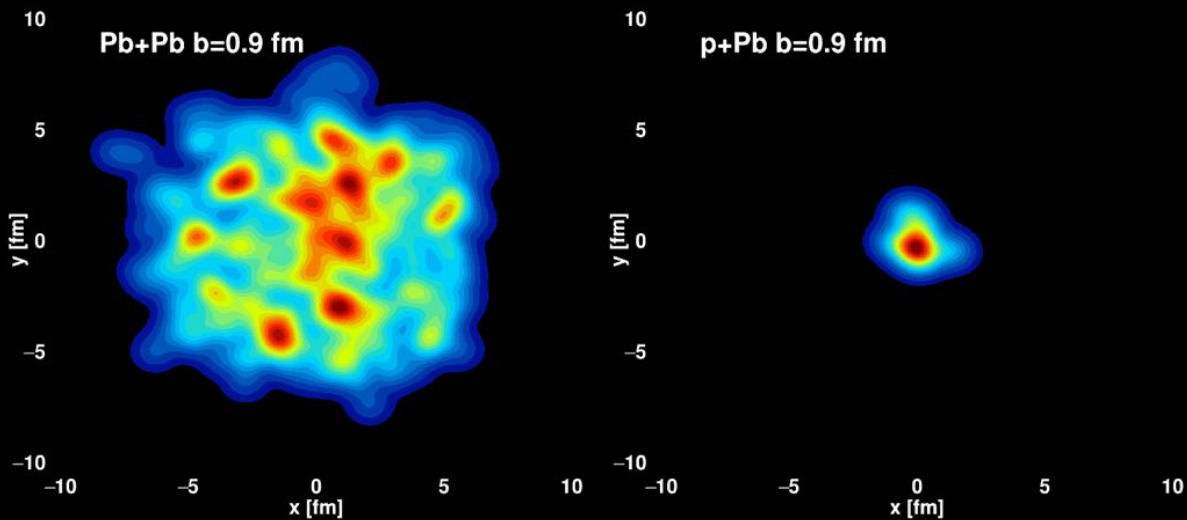
1 researcher (post-MS degree)

1 Administrative Assistant

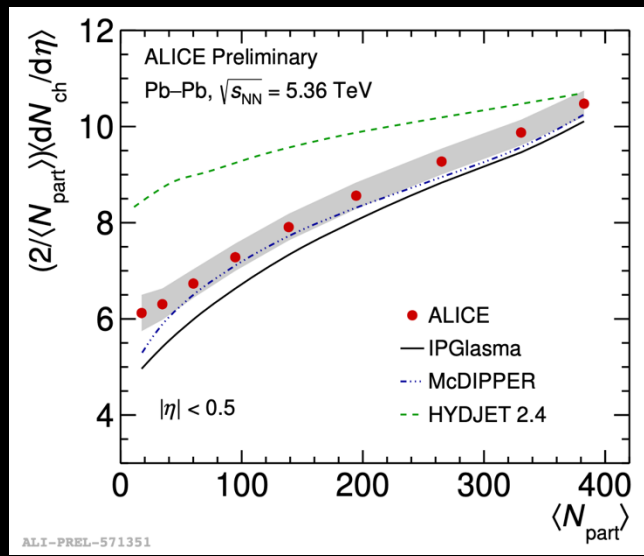
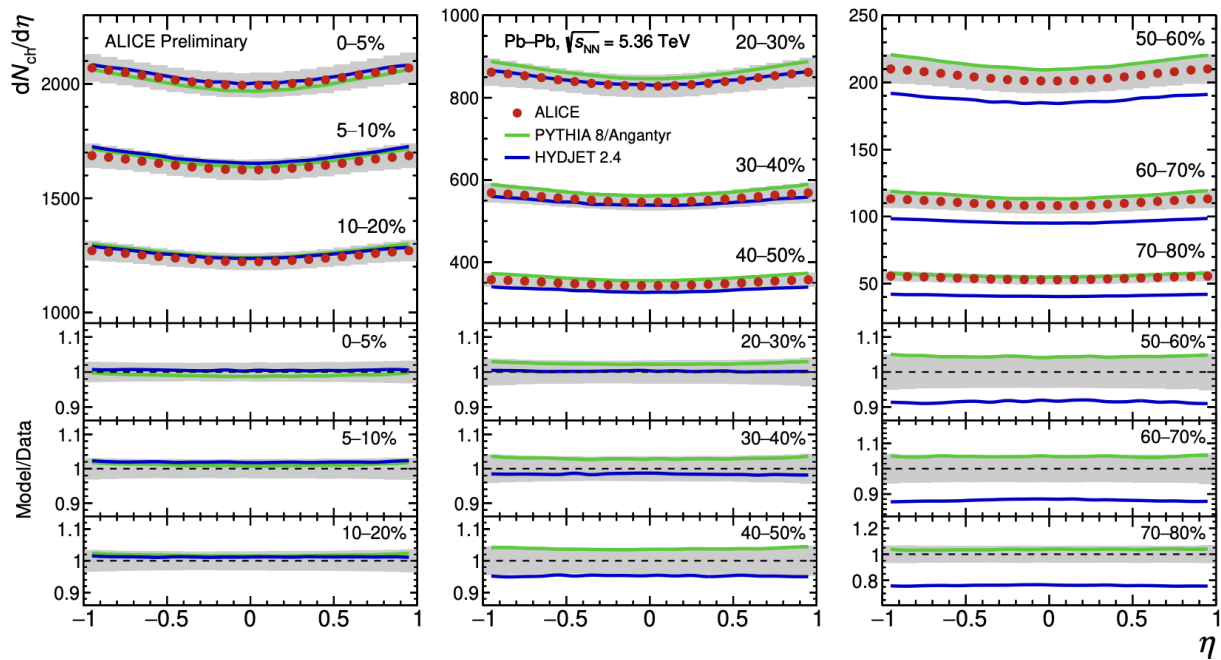
+1 PhD Physicists from KISTI (1 M&O-A)



Searching for a droplet of QGP? Controlling the size of QGP?



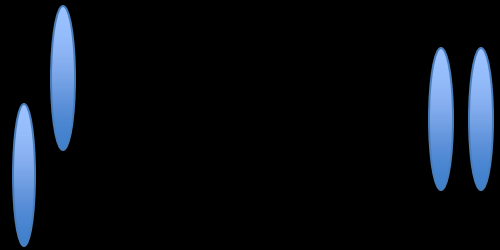
Searching for a droplet of QGP? Controlling the size of QGP?



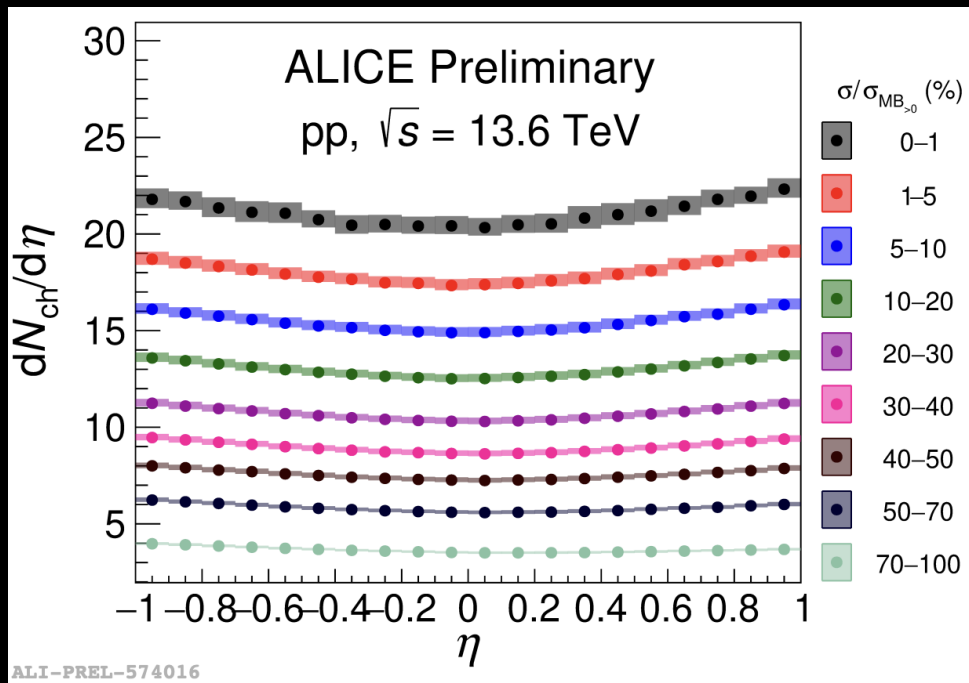
ALI-PREL-571351

ALI-PREL-571341

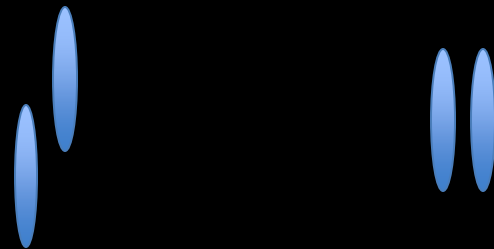
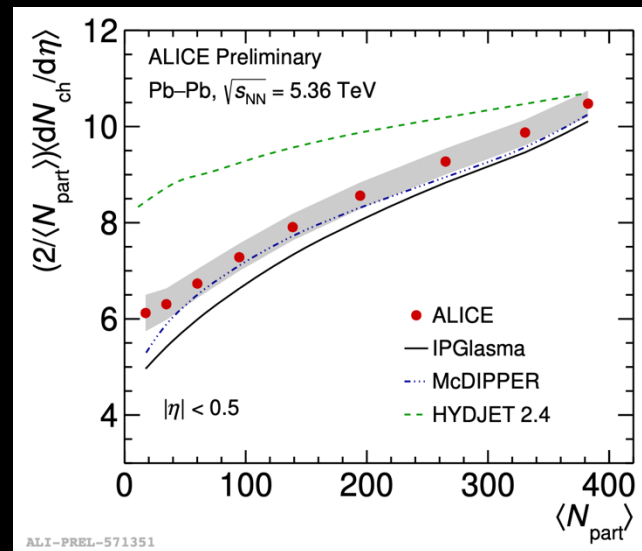
Charged particle pseudo-rapidity density in Pb-Pb at 5.36 TeV



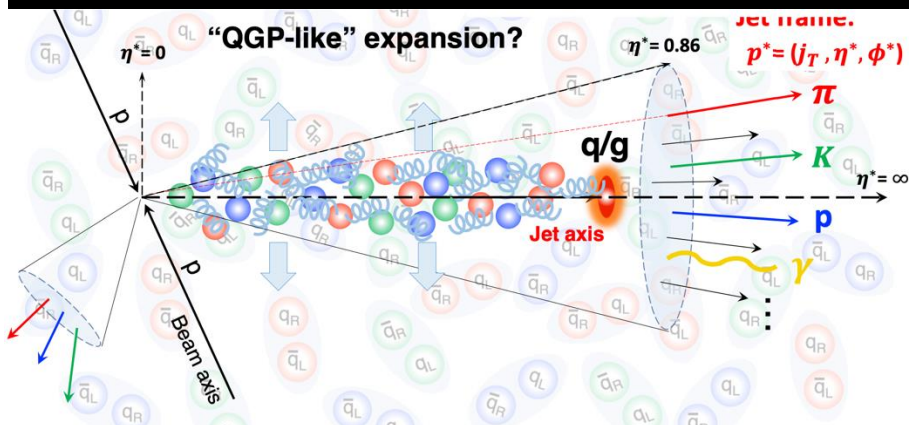
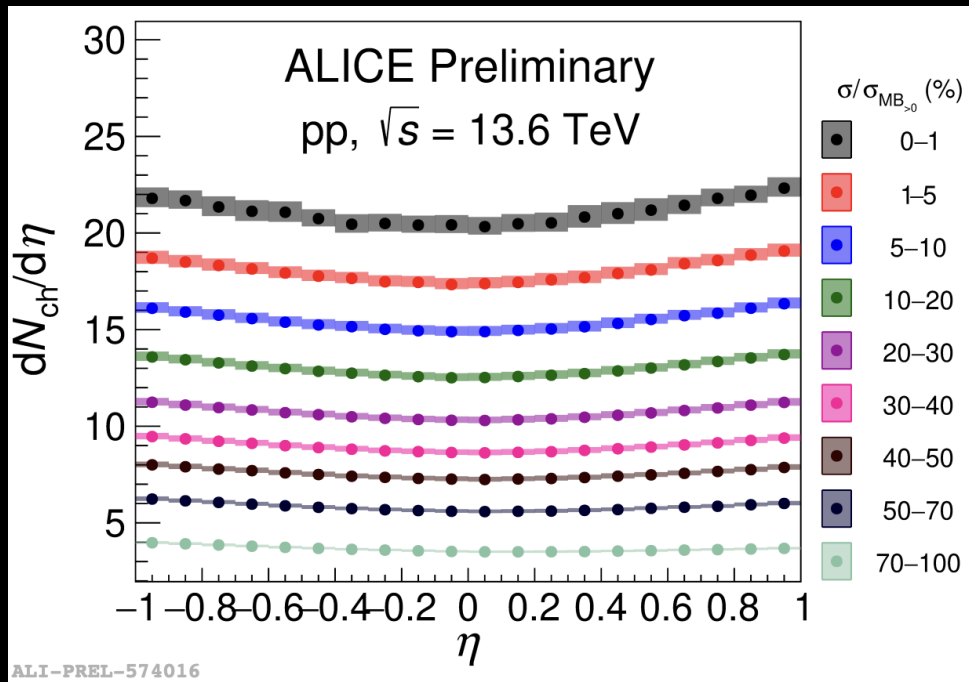
Searching for a droplet of QGP? Controlling the size of QGP?



Charged particle pseudo-rapidity density in pp at 13.6 TeV



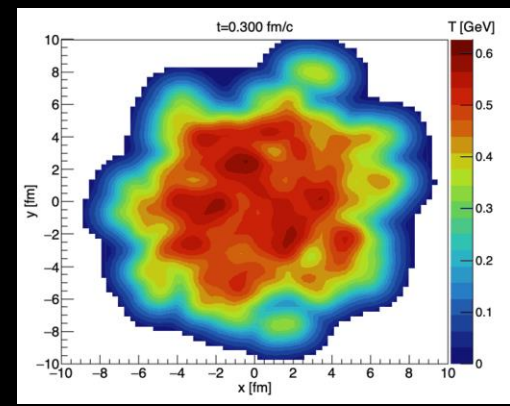
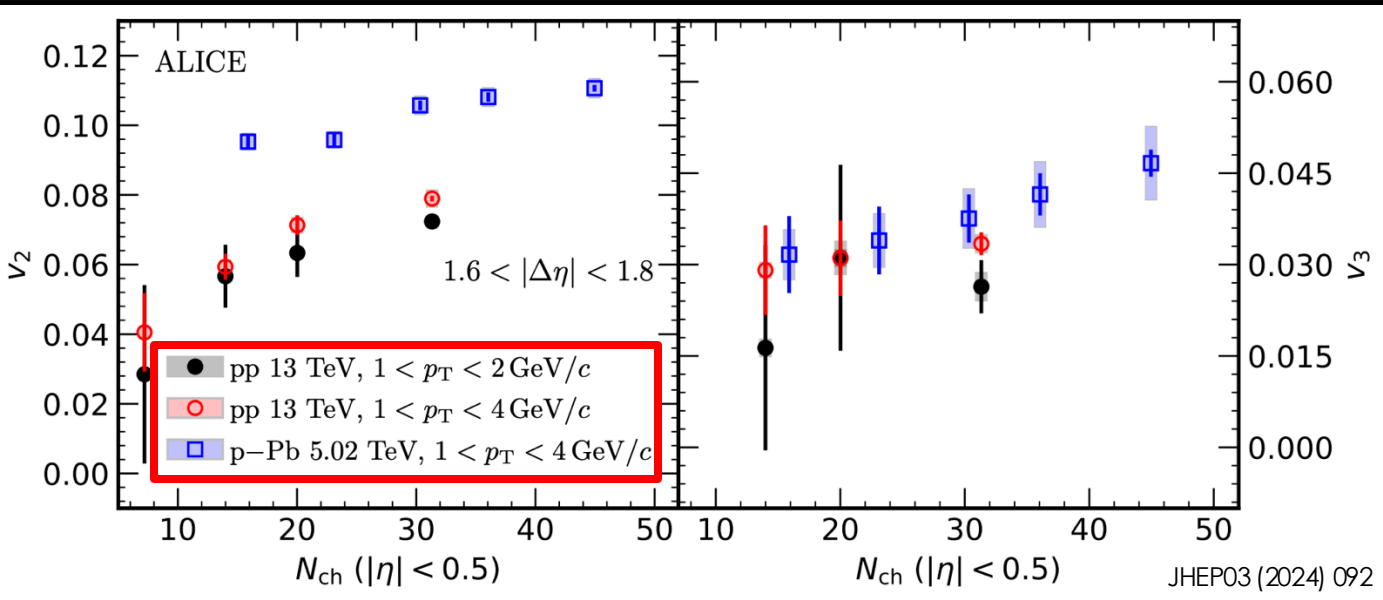
Searching for a droplet of QGP? Controlling the size of QGP?



More extreme environment inside a jet?

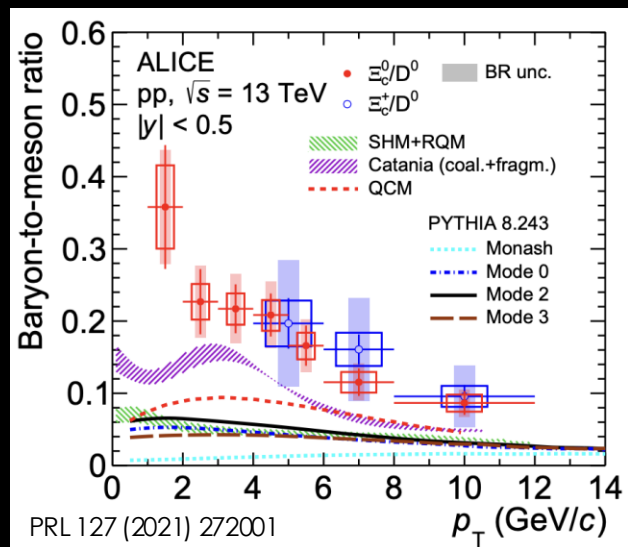
Charged particle pseudo-rapidity density in pp at 13.6 TeV

Searching for a droplet of QGP? Controlling the size of QGP?

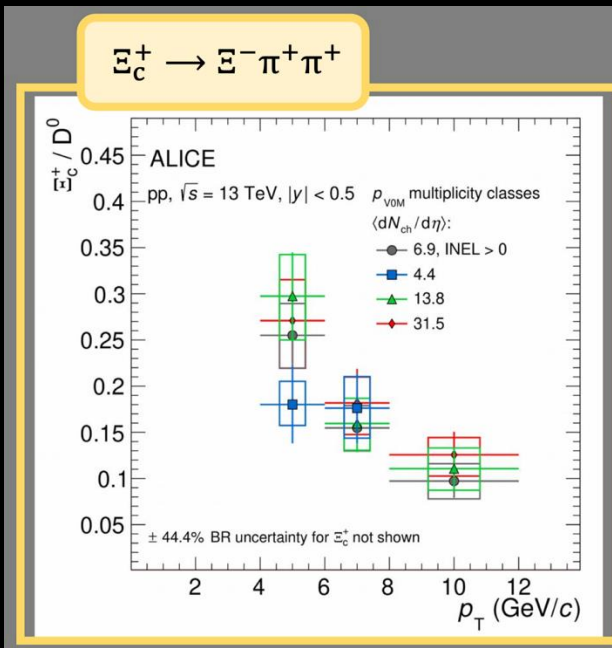


Clear collectivity in pp collisions

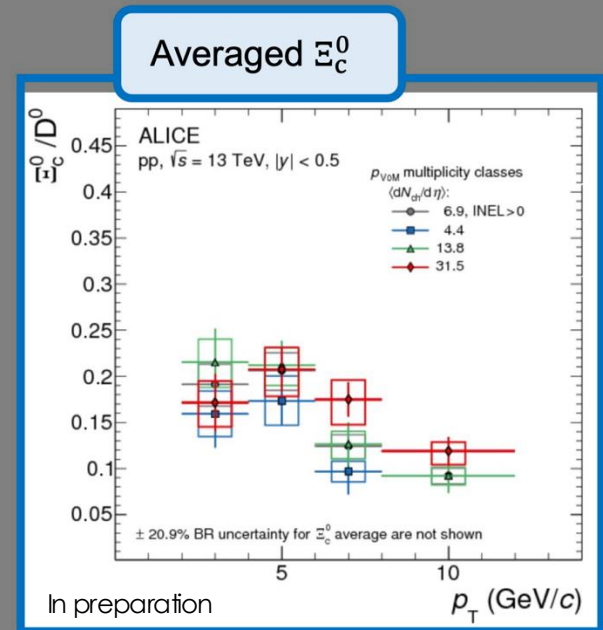
Searching for a droplet of QGP? Controlling the size of QGP?



Integrated multiplicity

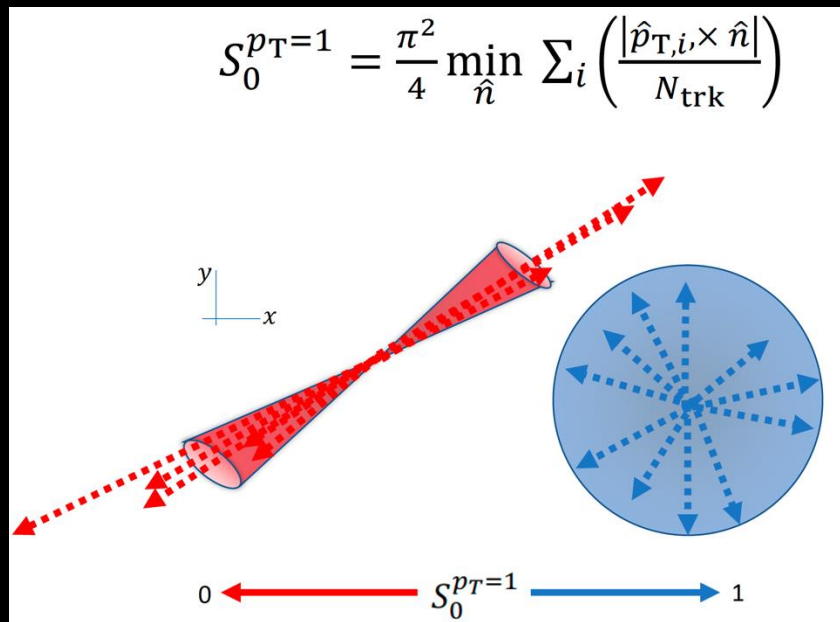


Multiplicity dependent

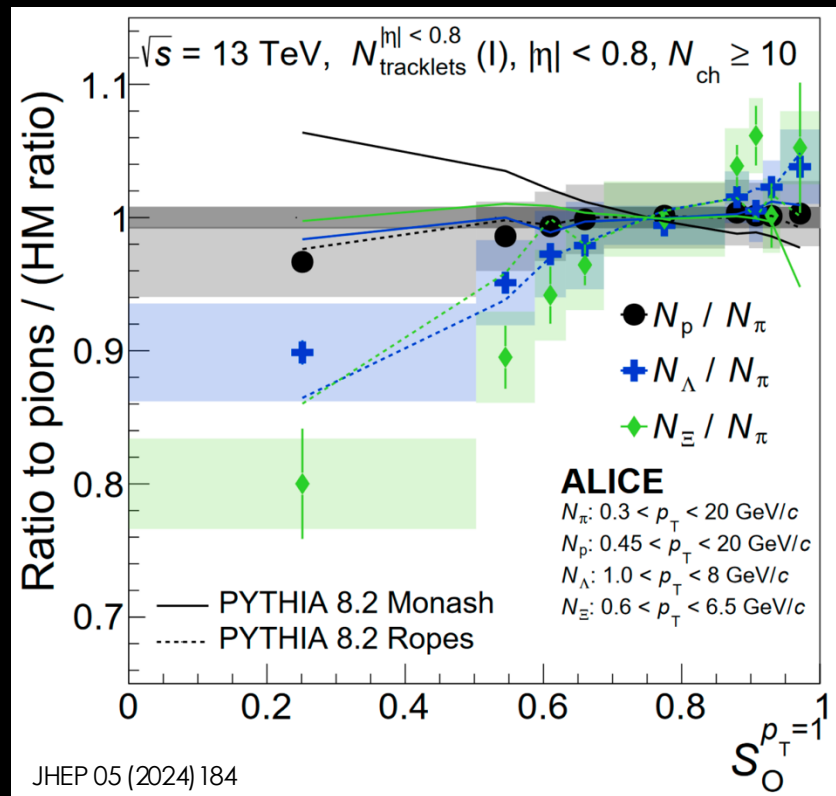


Charm fragmentation (hadronization) is not universal

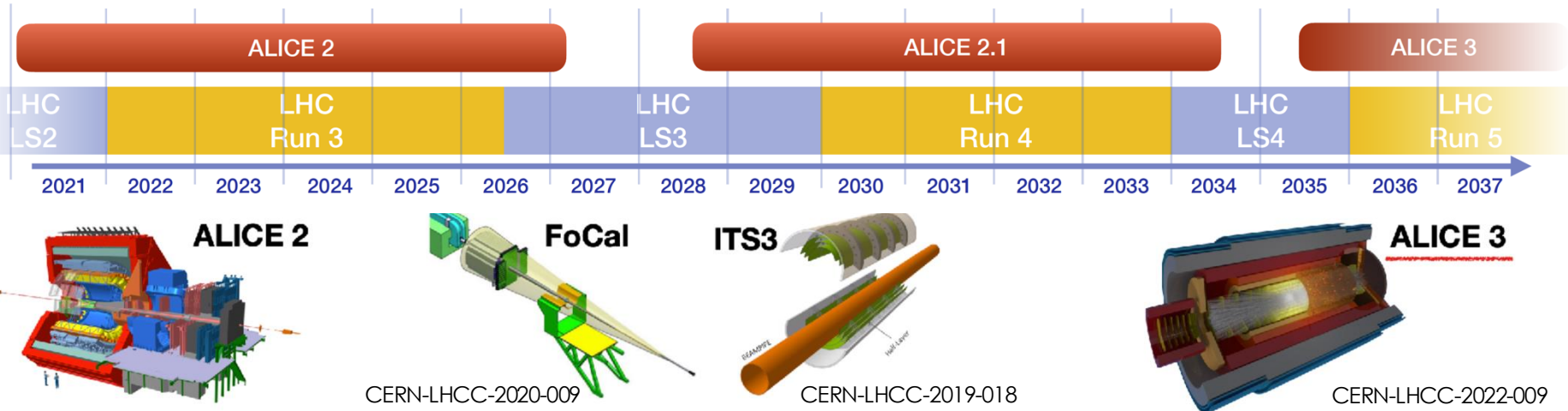
Searching for a droplet of QGP? Controlling the size of QGP?



Event classification for the top 1% high multiplicity:
jet-like vs isotropic



Strangeness enhancement is a property of underlying events



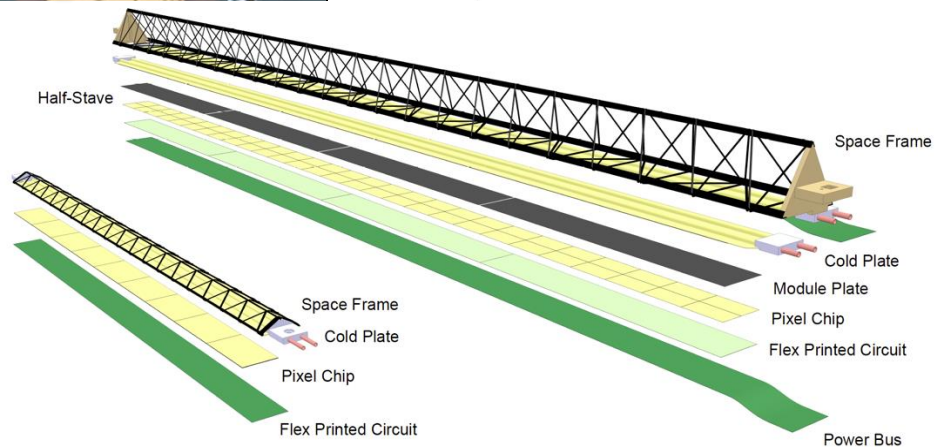
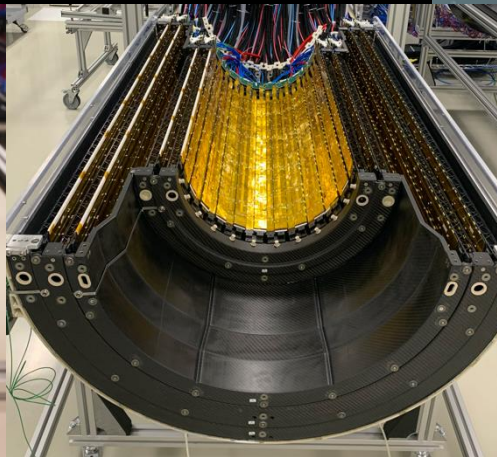
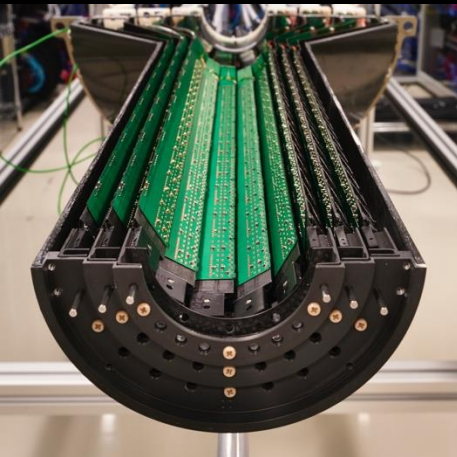
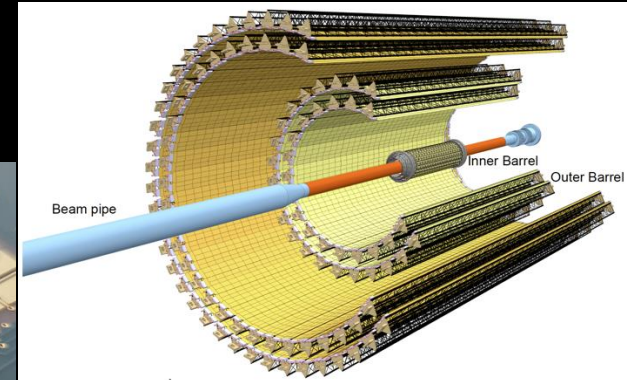
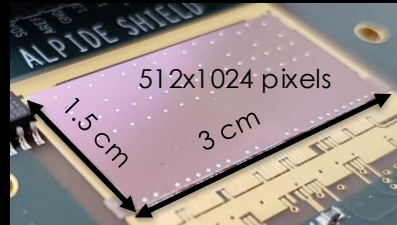
• FoCal

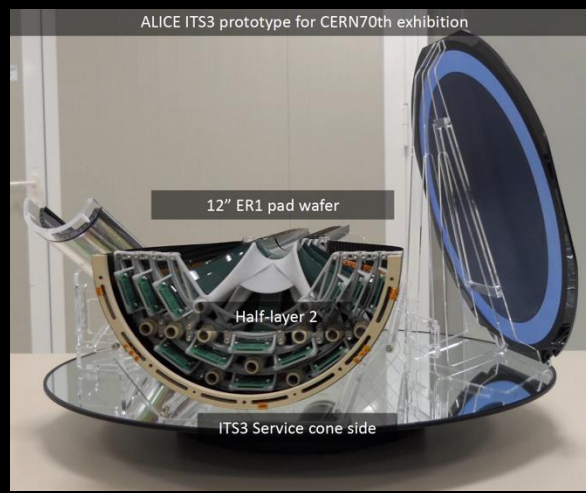
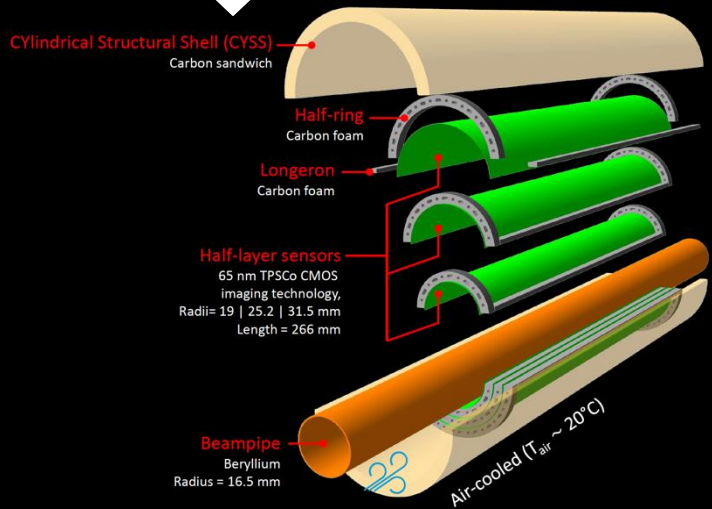
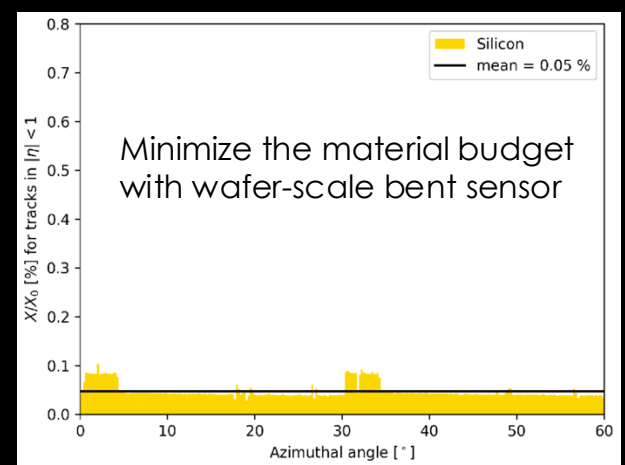
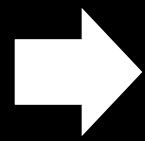
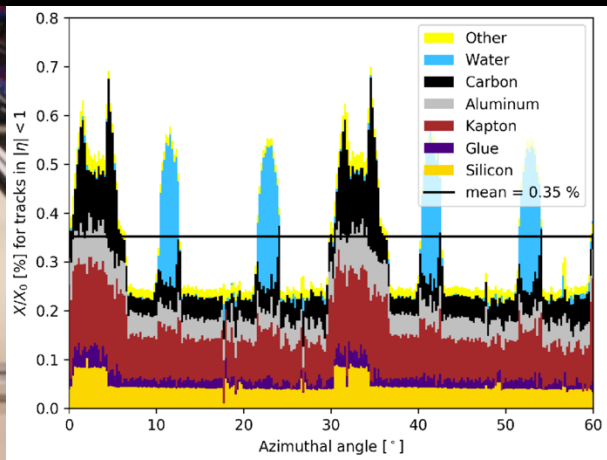
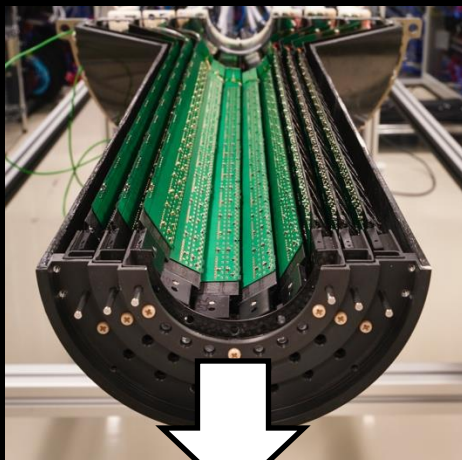
- FoCal-E: 20 layers of W ($3.5 \text{ mm} \approx 1 X_0$) + Si sensors
Two sensor types: pad and pixel (ALPIDE)
- FoCal-H: conventional metal-scintillator sampling calorimeter
- Parton distributions in protons and nuclei with photons and jets at forward rapidity

• ITS3

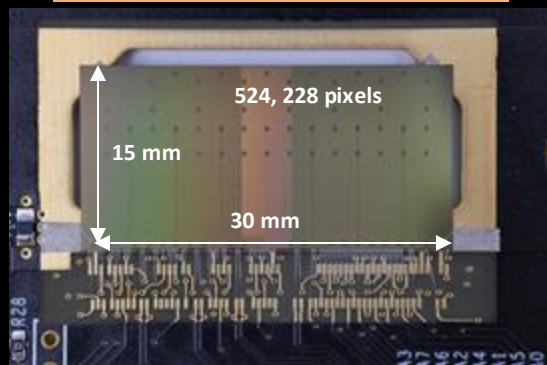
- Replacement of 3 innermost layers of ITS2 with curved wafer-scale silicon sensors
- low material budget: $0.05\% X_0$ per layer
- Improved tracking precision and efficiency at low p_T

- New inner tracking system (ITS2) for Run 3
 - 7 layers (3 inner + 4 outer)
 - Monolithic Active Pixel Sensor Technology
 - Pitch: $29 \times 27 \mu\text{m}^2$
 - Thickness: $50 \mu\text{m}$ for inner, $100 \mu\text{m}$ for outer
 - $5 \mu\text{m}$ position resolution, $>99\%$ hit efficiency





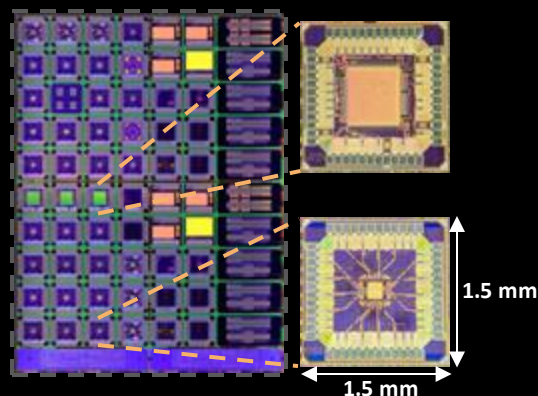
ALPIDE (ITS2, 180 nm)



ALice Pixel DEtector

- ▶ Manufactured with Tower Semiconductor 180 nm CIS
- ▶ 1024 x 512 pixels
- ▶ Used chip for ITS2
- ▶ 50, 100 μm thickness
- ▶ > 99 % detection efficiency
- ▶ Bent chip test + use reference planes detector in telescope

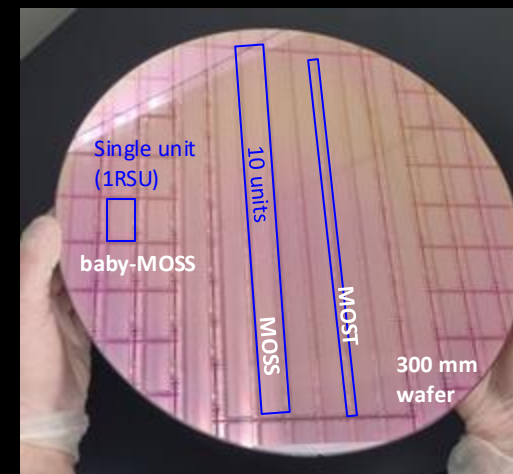
MLR1 (65 nm)



Multi-reticle Layer Run 1

- ▶ Qualifying the TPSCo 65 nm CIS
- ▶ 55 prototypes sensors
- ▶ Analog Pixel Test Structure (APTS)
 - 6 x 6 pixels
 - Direct analog readout of central 4 x 4
 - 10, 15, 20, 25 μm pitches
- ▶ Digital Pixel Test Structure (DPTS)
 - 32 x 32 pixels
 - Asynchronous digital readout

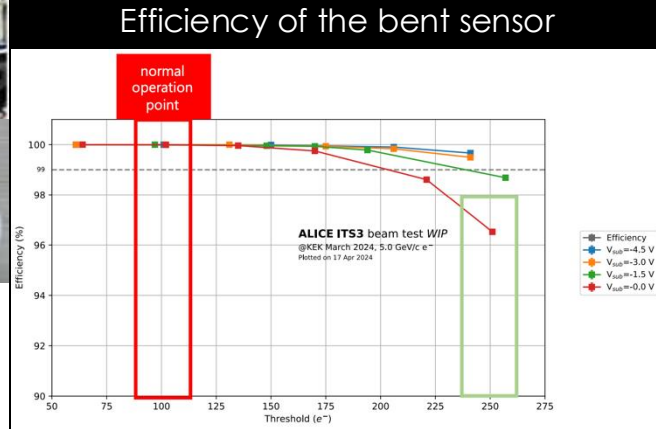
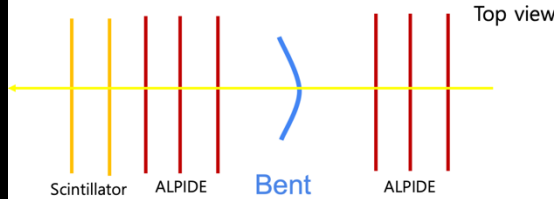
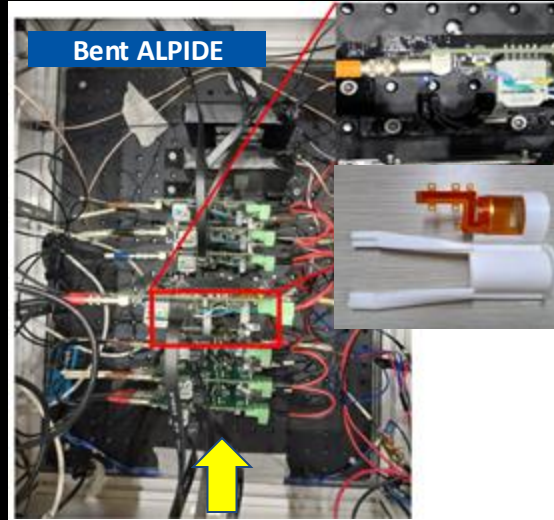
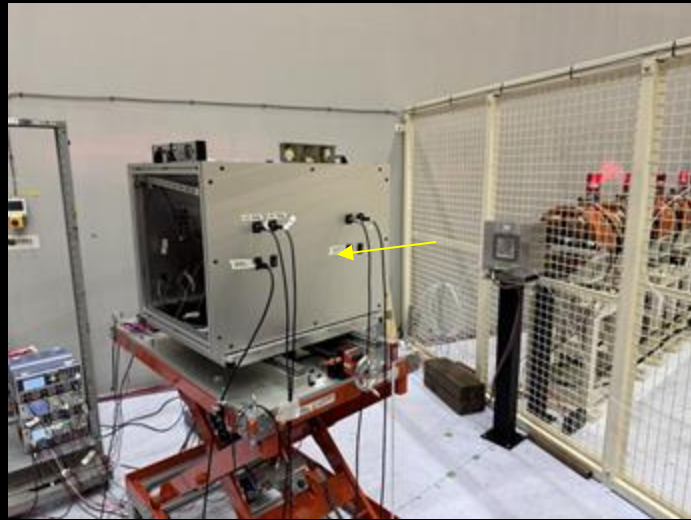
ER1 (65 nm)



Engineering Run 1

- ▶ First MAPS for HEP using stitching
- MOSS: 14 x 259 mm, 6.72 MPixels (22.5 x 22.5, 18 x 18 μm^2)
 - ▶ Conservative design
 - ▶ Different pitches
- MOST: 2.5 x 259 mm, 0.9 MPixels (18 x 18 μm^2)
 - ▶ More dense design

Develop a telescope and perform a beam test (KEK PF-AR)



Still >99% efficiency after bending

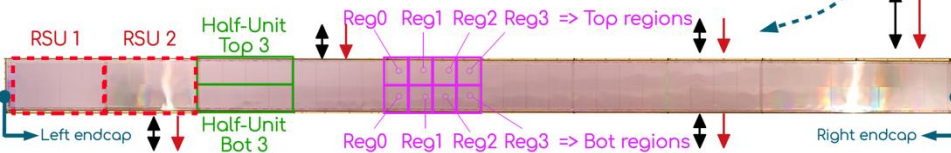
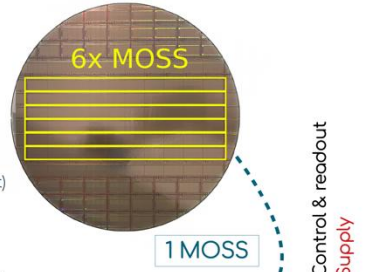
Consistent results with the results from the ALICE ITS3 team

The paper is under preparation

- ▶ Collaboration with Japanese colleagues
- ▶ Electron beam @ 3 - 5 GeV/c
- ▶ Various DUT sensors have been studied
 - Bent ALPIDE
 - APTS-SF
 - CE65v2

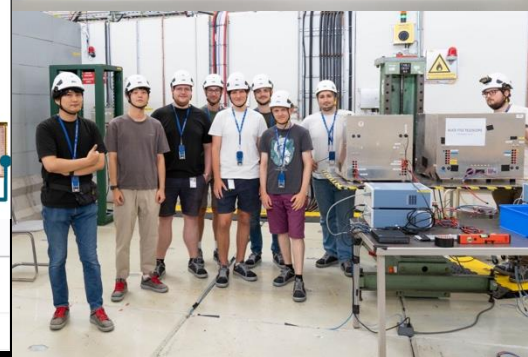
Participation in babyMOSS lab test and beam test (CERN PS)
 KoALICE group will produce a new telescope with babyMOSS
 (beam test at KEK PF-AR in early next year)

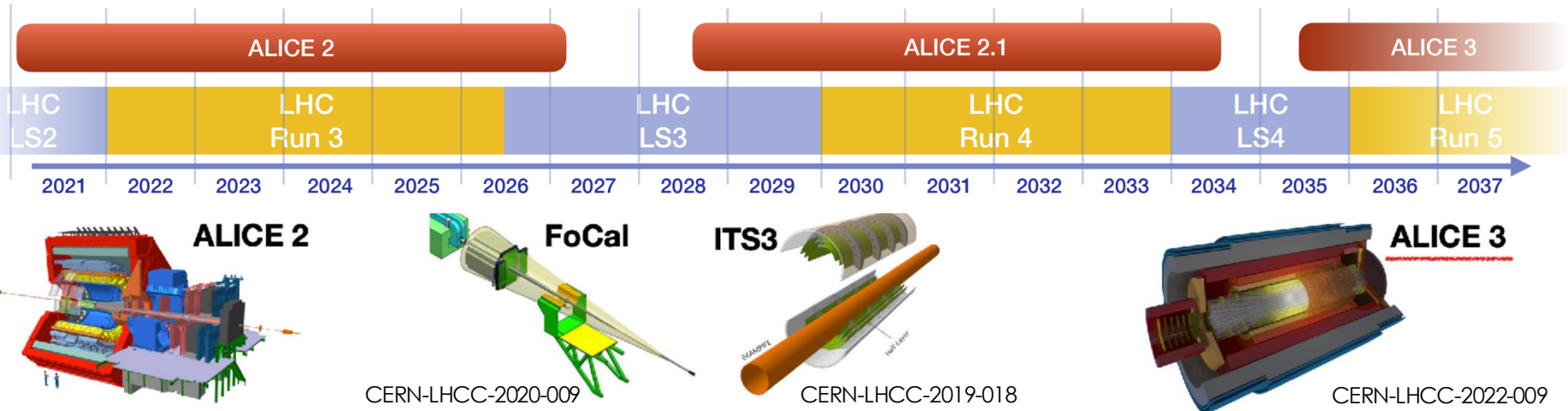
- MOnolithic Stitched Sensor (ER1 sensor) – 14x259 mm²
- 10 Repeated Sensor Units (RSU)
- 20 Top/Bot independent Half Units (HU)
- 4 regions per HU:
 - Top regions: 256x256 pixels, 22.5 μm pitch (conservative layout)
 - Bot regions: 320x320 pixels, 18 μm pitch (compact layout)
- 8 power nets per HU (AVDD, AVSS, DVDD, DVSS, IOVDD, BBVDD, BBVSS, PSUB)
- HUs can be powered, readout and controlled individually



Analogue in-pixel frontend

| | Region 0 | Region 1 | Region 2 | Region 3 |
|--------|----------|------------------------------|---|--------------------------------------|
| TOP | Standard | Larger input transistor (M1) | Larger discriminator input transistor (M11) | Larger common-source transistor (M2) |
| BOTTOM | Standard | Standard | Standard | Slightly different layout |





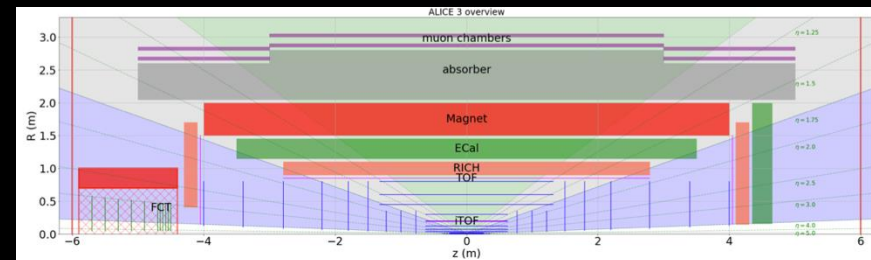
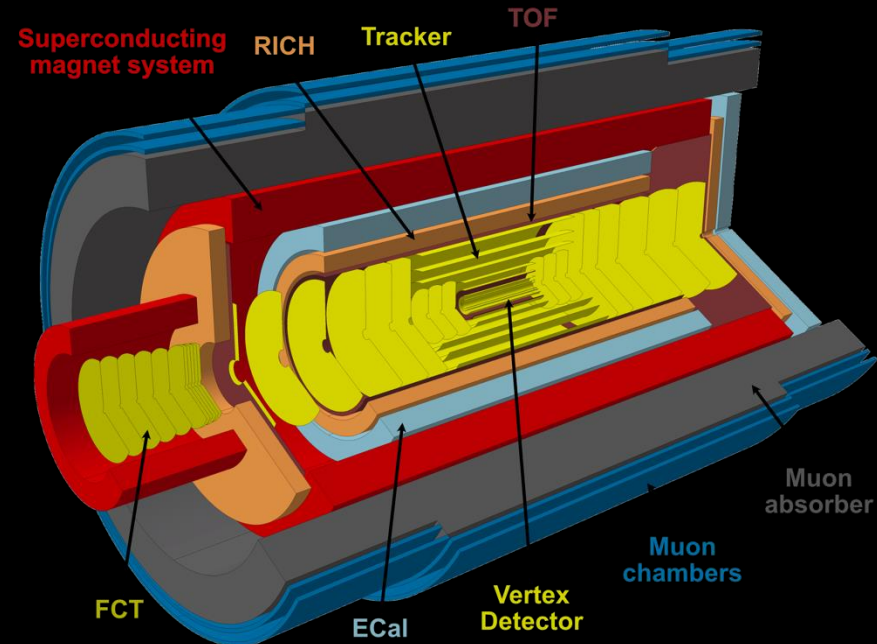
• Heavy-ion physics at the LHC beyond Run 4

- Parton transport: high-precision beauty measurements
- Formation of hadrons: multi-charm baryons, P-wave quarkonia, exotic hadrons
- Bulk and shear viscosity: azimuthal asymmetry of electromagnetic radiation
- Chiral symmetry restoration: low mass dileptons
- Collectivity in small systems: high event rates and a large acceptance



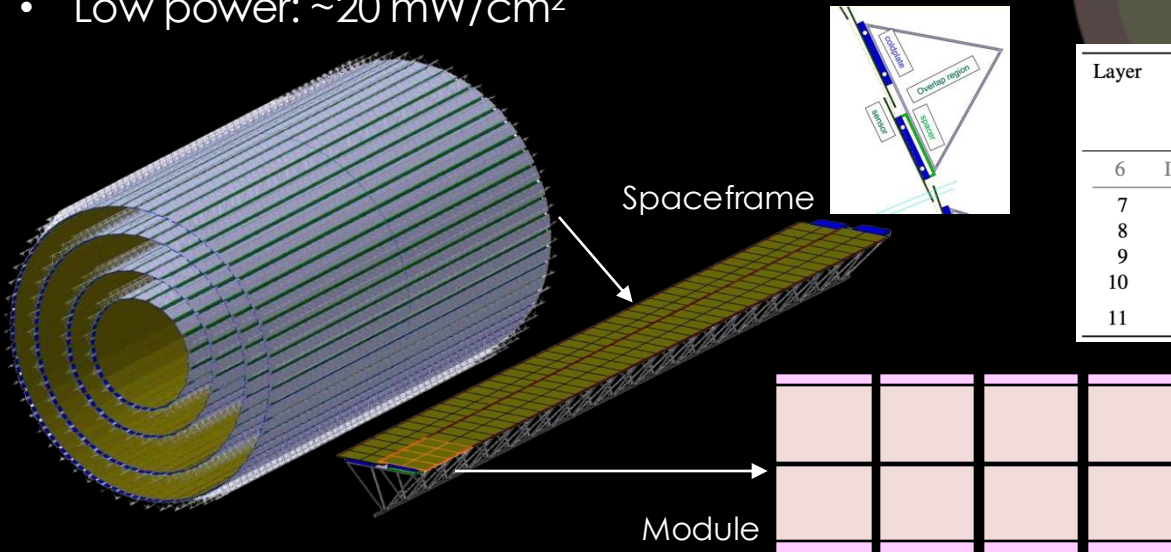
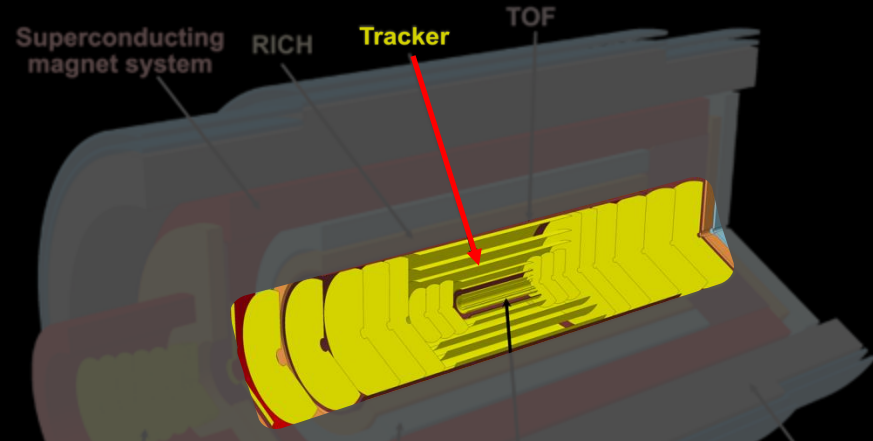
ALICE 3: Detector Overview

- Compact and large acceptance
 - $|\eta| < 4$ and $p_T > 0.02$ GeV/c
- Superconducting magnet system
 - Maximum field: $B=2$ T
- All silicon-based large acceptance tracker
 - $\sim 10\%$ X_0 overall material budget
 - ~ 10 μm pointing resolution at $p_T \sim 200$ MeV/c
- Particle identification in a wide p_T and η range
 - Silicon-based TOF and RICH
 - Muon identification
- Continuous readout and online processing



ALICE 3: Outer Tracker

- 8 layers and 9 disks based on MAPS
 - Total of $\sim 60\text{m}^2$ of silicon
 - Compact design ($R < 80\text{ cm}$, $|z| < 4\text{ m}$)
- Pixel pitch of $\sim 40\ \mu\text{m}$ for $\sim 10\ \mu\text{m}$ intrinsic resolution
- 1% X_0 per layer
- Low power: $\sim 20\text{ mW/cm}^2$



| Layer | Det. | Material thickness (% X_0) | Intrinsic resolution (μm) | Barrel layers | | Forward disks | |
|-------|-------|-------------------------------------|--|------------------------------------|------------------------|----------------------------|--------------------------|
| | | | | Full length (Δz) (cm) | Radius (r) (cm) | Position ($ z $) (cm) | $R_{in}-R_{out}$ (cm) |
| 6 | IT/OT | 1 | 10 | 1×124 | 20 | 150 | 5-68 |
| 7 | OT | 1 | 10 | 1×129 | 30 | 180 | 5-68 |
| 8 | OT | 1 | 10 | 2×129 | 45 | 220 | 5-68 |
| 9 | OT | 1 | 10 | 2×129 | 60 | 260 | 5-68 |
| 10 | OT | 1 | 10 | 2×129 | 80 | 300 | 5-68 |
| 11 | OT | 1 | 10 | | | 350 | 5-68 |

Path to the module after sensor fabrication

Sensor test procedure for ITS2

for ALICE 3 OT

1,500 raw wafers

Raw Wafer Production
MEMC (Italy)

5%

Raw Wafer QA
TMEC (Thailand)

1,200 CMOS wafers
1,920 CMOS wafers

CMOS Manufacturing
TowerJazz (Israel)

8%
(2/25)

Wafer Probe Testing
CERN

55,000 sensors
109,200 sensors

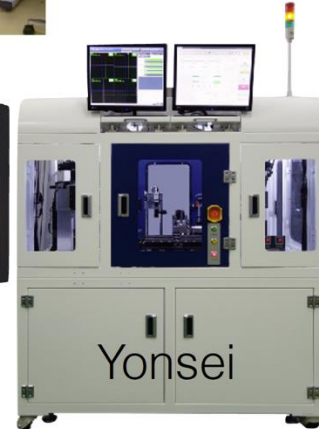
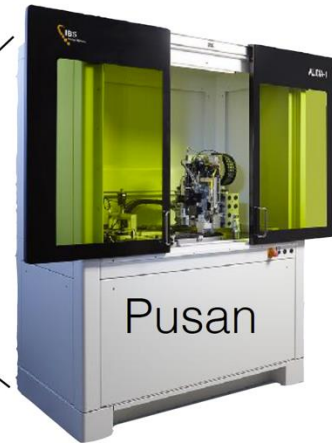
Thinning & Dicing
FUREX (South Korea)

Pick & Place
FUREX (South Korea), tbc.

100%

Chip Series Testing
Yonsei, Pusan/Inha
(South Korea)

Detector assembly



Chip-level or wafer-level test

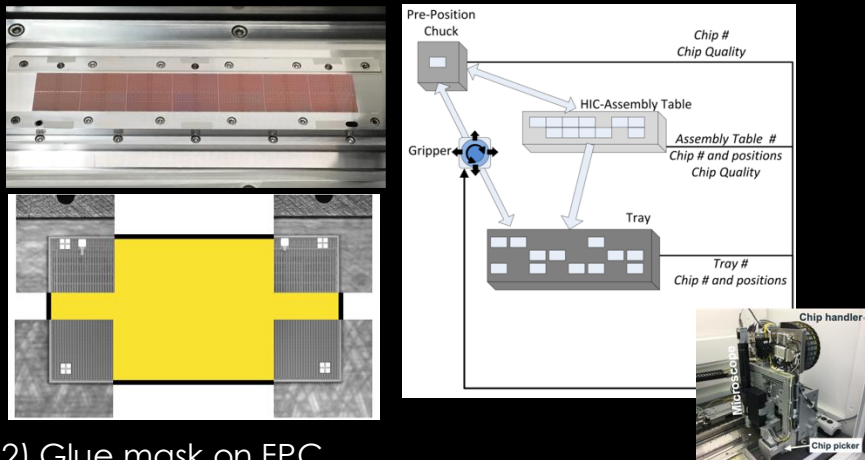
Under discussion with a wafer probing company in Korea for a test run

Path to the module after sensor fabrication

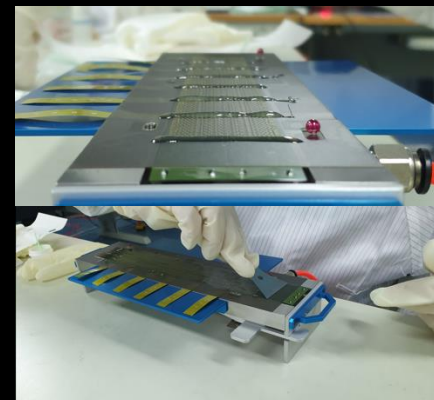
Module assembly procedure for ITS2 OB
2600 modules for ~2 years in 5 sites

ALICE 3 OT:
5620 for barrel and 2688 for disks
~10000 modules considering yield and spares

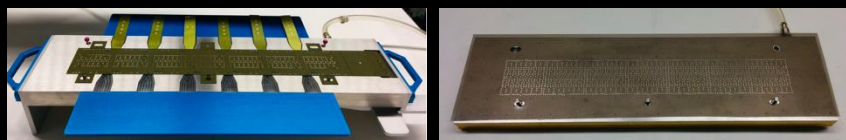
1) Chips positioned on the HIC table



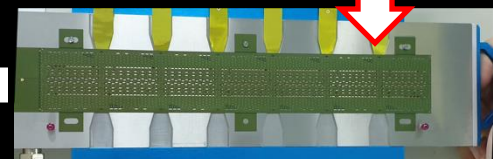
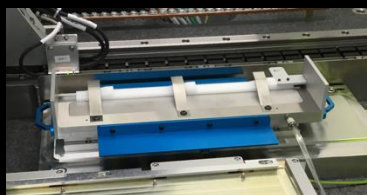
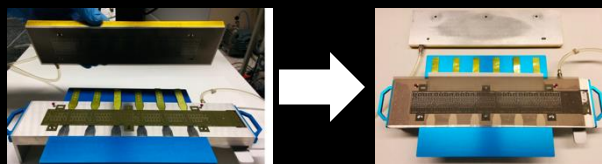
3) Gluing and curing



2) Glue mask on FPC



~5 hours curing time



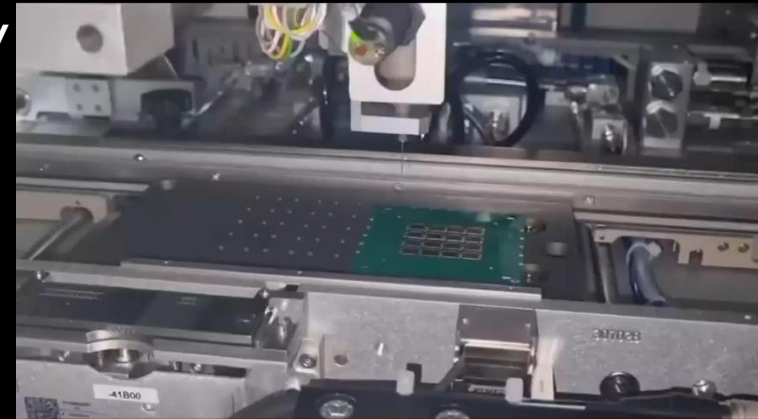
- **Automatization and industrialization of module assembly**
 - Collaboration with MEMSPACK using a multi-purpose machine die bonder



Datacon 2200 evo+



MRSI



Integrated Dispenser

- Pressure/time (Musashi®), Auger, Jetter types available
- Epoxy stamping option
- Filled and unfilled epoxy, wide viscosity range
- Small footprint, low cost-of-ownership



Vision Alignment

- New high-speed image processing unit
- Full alignment & Bad mark search
- Pre-defined fiducial geometry & customized teaching



Visit from Japan



Visit from Germany



Automatic Wafer and Tool Changer

- Fully Automatic cycle for Multi-Chip production
- Up to 7 Pick & Place tools (optionally 14), 5 eject tools
- Stamping tools and calibration tools possible



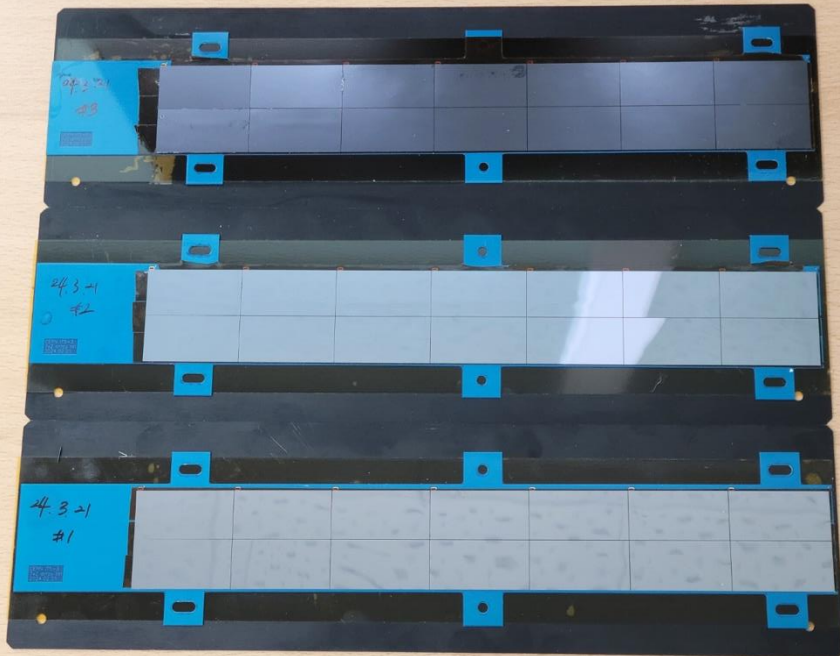
Pick & Place Head

- Die Attach, Flip Chip and Multi-Chip in one machine
- Die pick from: wafer, wafler pack, Gel-Pak®, feeder
- Die place to: substrate, boat, carrier, PCB, leadframe, wafer
- Hot and cold processes supported: epoxy, soldering, thermo-compression, eutectic



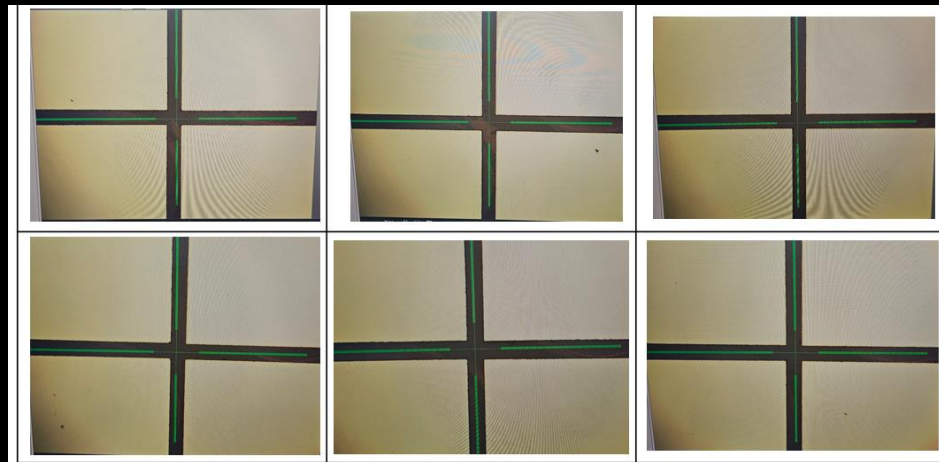
Dummy module assembly (2024 March)

- Machine validation using dummy chips and dummy boards
 - Both for ITS2 OB HIC design and ALICE 3 OT design
 - Thicker chip (50-100 μm) and board (0.3 mm) to validate the repeatability of position precision
 - Successfully produced five modules with good position precision (using double-sided tape)



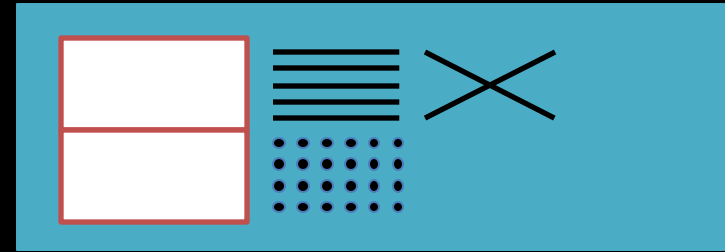
| Measure# | PP-X | PP-Y | Distance |
|----------|--------------|------|--------------|
| 1 | 30.149999 mm | 0 mm | 30.149999 mm |
| 2 | 30.15 mm | 0 mm | 30.15 mm |
| 3 | 30.149999 mm | 0 mm | 30.149999 mm |
| 4 | 30.15 mm | 0 mm | 30.15 mm |
| 5 | 30.15 mm | 0 mm | 30.15 mm |
| 6 | 30.149999 mm | 0 mm | 30.149999 mm |

| Measure# | PP-X | PP-Y | Distance |
|----------|--------------|--------------|--------------|
| 1 | -0.000002 mm | 15.15 mm | 15.15 mm |
| 2 | -0.000002 mm | 15.15 mm | 15.15 mm |
| 3 | 0 mm | 15.149999 mm | 15.149999 mm |
| 4 | 0 mm | 15.149999 mm | 15.149999 mm |
| 5 | 0 mm | 15.15 mm | 15.15 mm |
| 6 | 0 mm | 15.149999 mm | 15.149999 mm |
| 7 | 0 mm | 15.15 mm | 15.15 mm |



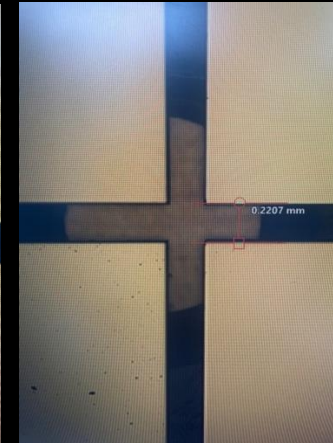
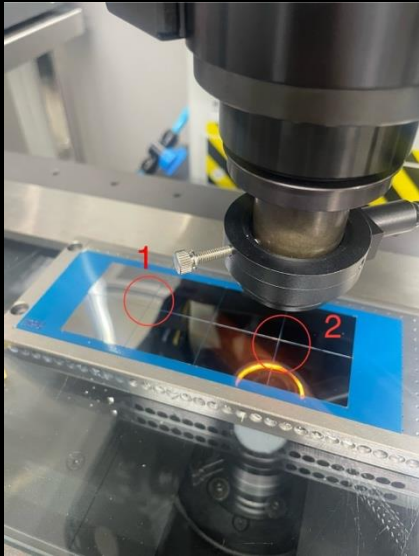
Dummy module assembly (2024 June)

- Die bond with heat cure epoxy
 - Epoxy generally used by MEMSPACK
 - Heat cure condition: 100 °C, 30 minutes (outside from the die bonder machine)
 - Dispense epoxy on the PCB (a few lines) and place chips
 - 0.3 mm thick chip (will reduce gradually)
 - Various dispensing patterns to minimize the position variation



Dummy module assembly (2024 June)

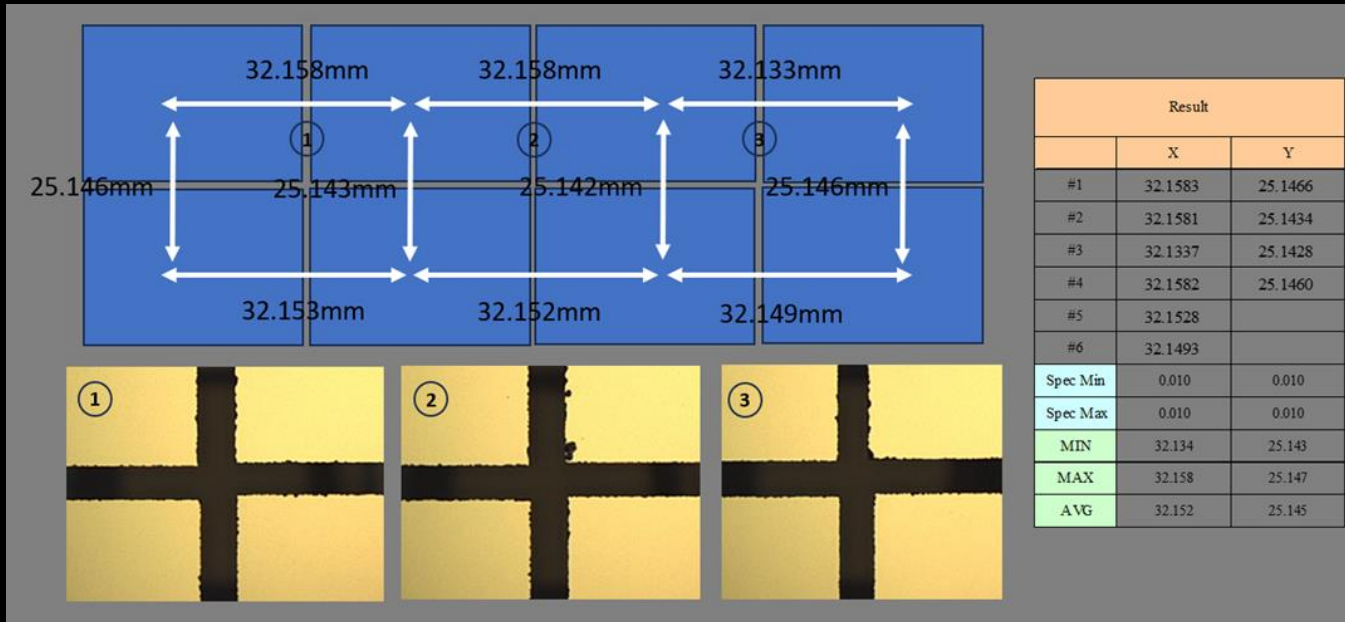
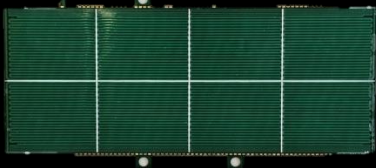
- Die bond with heat cure epoxy
 - Epoxy generally used by MEMSPACK
 - Heat cure condition: 100 °C, 30 minutes (outside from the die bonder machine)
 - Dispense epoxy on the PCB (a few lines) and place chips
 - 0.3 mm thick chip (will reduce gradually)
 - Various dispensing patterns to minimize the position variation
 - Reasonable position precision but needs to be optimized



Dummy module assembly (2024 October)

- Die bond with heat cure epoxy
 - Epoxy generally used by MEMSPACK
 - Heat cure condition: 100 °C, 30 minutes (outside from the die bonder machine)
 - Dispense epoxy on the PCB (a few lines) and place chips
 - 0.3 mm thick chip (will reduce gradually)
 - **Confirmed a good position precision**

- To do
 - Thinner chip
 - Flexible PCB
 - Wire bonding
 - Epoxy (Araldite 2011)



Concept of mass production procedure

- Uses several assembly jigs to run the assembly station continuously
 - FPCB is held with a vacuum during curing
 - Plan to build the system and verify the procedure
 - Expected production rate: 20-30 modules (chips+FPCB) per day, even with Araldite 2011

Assembly jig



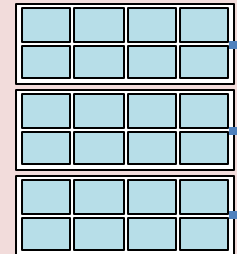
Assembly station
(die bonder machine)



Jig station



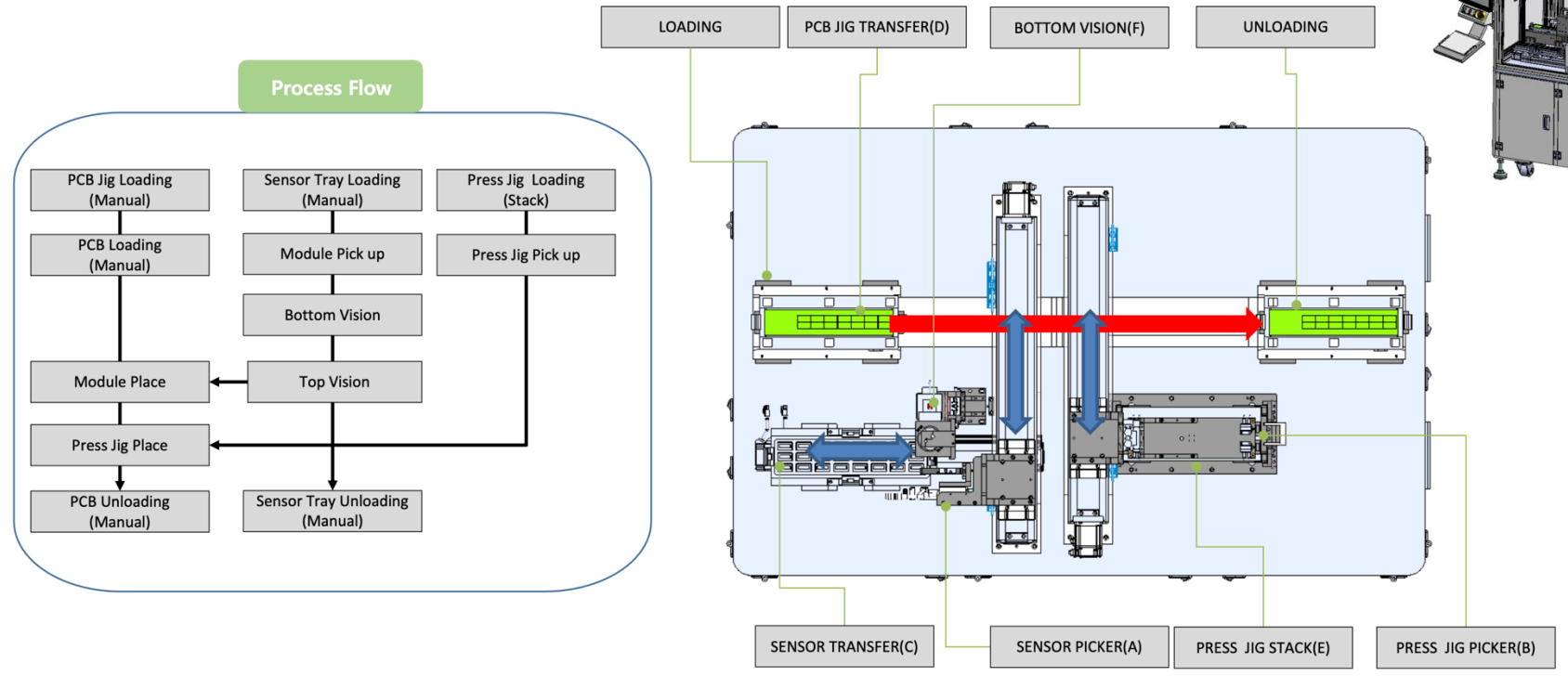
Curing station



Vacuum
line

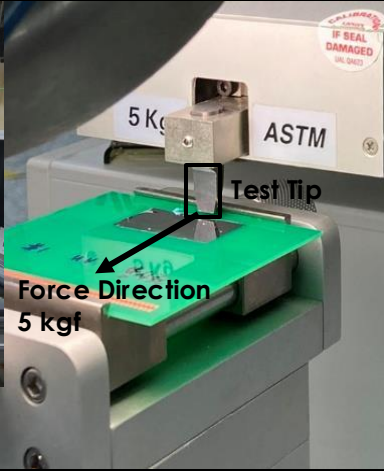
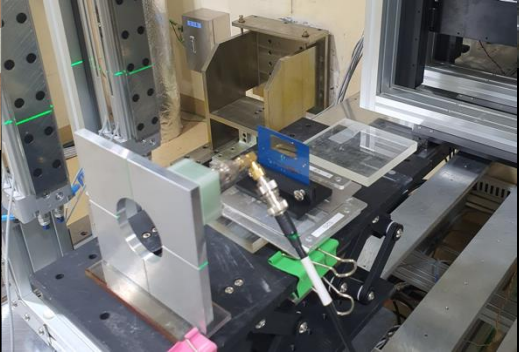
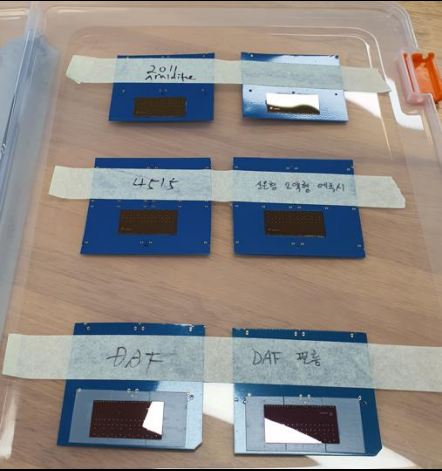
Customized module assembly machine (C-ON tech)

- Initial design for the customized machine
 - Chip handling system will provide an accurate position precision
 - Plan to produce a prototype machine in 2025



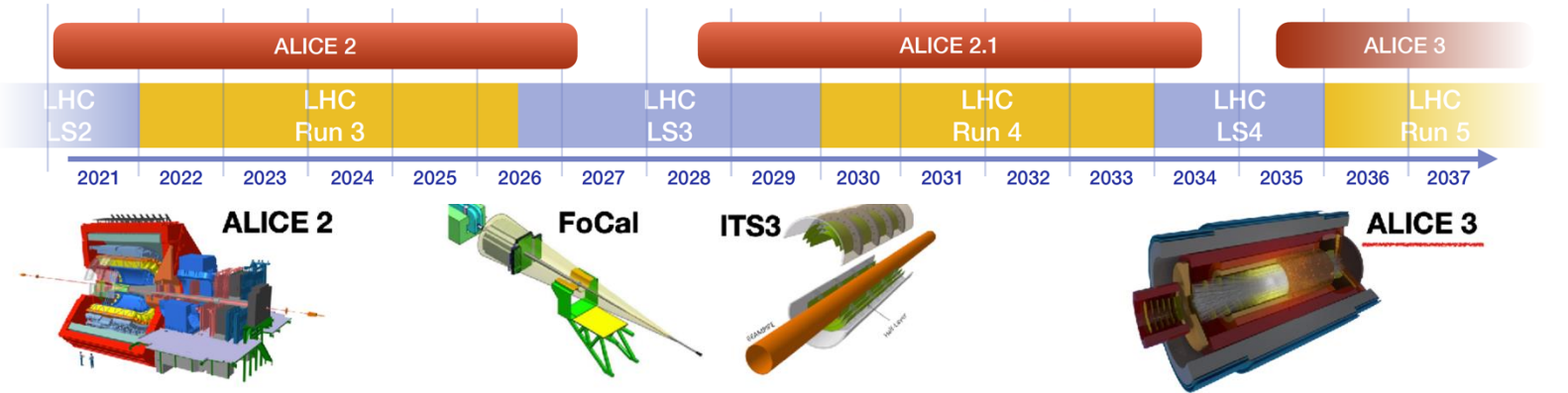
Radiation hardness test

- Proton beams (15~20 MeV) at KOMAC TR23 can be utilized for radiation hardness test of epoxies
 - High-intensity beams (10^{10-11} #/cm² s)
 - Comparison between different epoxies, including Araldite 2011
 - First run in Oct/16-17 and second run in Dec/23-24





KEEP MOVING
FORWARD



BACKUP